Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	3681	polymeriz\$5 near5 monomer and particles near6 (substrate wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 14:49
L2	1511	1 and catal\$4 and size near3 particles	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 14:49
L3	566	2 and (detect\$34 measur\$3) with particle	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 14:32
L4	241	3 and laser	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 14:27
L5	50	4 and scanner	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 14:27
L6	547	2 and (detect\$34 measur\$3) near15 particle	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 14:50
L7	159	6 and counter	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 14:36
L8	10	6 and particle near counter	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 14:33
L9	10	2 and particle near counter	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 14:36

L10	166	polymeriz\$5 near5 monomer and particles near6 (wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 14:49
L11	185	polymeriz\$5 near5 monomer and particles near9 (wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 14:49
L12	262	polymeriz\$5 near5 monomer and particles with(wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 14:49
L13	75	12 and catal\$4 and size near3 particles	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 14:49
L14	48	13 and (detect\$34 measur\$3) near15 particle	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 14:50

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	793	monomer and laser near scanner	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 15:34
L2	2	monomer near9 wafer and particles and laser near scanner	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 15:34
L3	280	polymeriz\$4 near5 monomer and laser near scanner	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 15:41
L4	244	3 and (particle defects)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 15:38
L5	198	3 and size near3 (particle defects)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 15:35
L6	64	3 and (size and number) near3 (particle defects)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 15:37
L7	7	3 and (size and number) near3 (particle defects) and wafer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 15:37
L8	6	3 and (particle defects) with wafer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 15:39
L9	6	3 and (particle) with wafer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 15:39

L10	233	3 and (particle)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 15:39
L11	66	10 and catalyz\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 15:40
L12	6	11 and particle near7 (metal copper)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 15:43
L13	43	plurality near5 monomer and laser near scanner	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 15:48
L14	14	13 and particle near7 (metal copper)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 15:42
L15	53	3 and particle near7 (metal)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 15:43
L16	11	plurality near5 monomer and particle near9 wafer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/06 15:48